



US 20240215120A1

(19) **United States**

(12) **Patent Application Publication**  
**HARADA et al.**

(10) **Pub. No.: US 2024/0215120 A1**

(43) **Pub. Date: Jun. 27, 2024**

(54) **FILM HEATER AND HEATER-EQUIPPED GLASS**

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(21) Appl. No.: **18/288,247**

(22) PCT Filed: **Apr. 25, 2022**

(86) PCT No.: **PCT/JP2022/018733**

§ 371 (c)(1),

(2) Date: **Oct. 25, 2023**

(30) **Foreign Application Priority Data**

Apr. 26, 2021 (JP) ..... 2021-074132

**Publication Classification**

(51) **Int. Cl.**  
**H05B 3/86** (2006.01)

**H05B 3/22** (2006.01)

(52) **U.S. Cl.**  
CPC ..... **H05B 3/86** (2013.01); **H05B 3/22** (2013.01)

(57) **ABSTRACT**

A film heater includes: a substrate; a first hard coat layer containing a first resin component and a silica filler; a first dielectric layer; a metal layer containing one or both of silver and silver alloy; a second dielectric layer; and an ITO layer or an IZO layer in the order presented, wherein a thickness of the metal layer is 5.5 to 7.5 nm, and wherein a peak intensity indicating a K $\alpha$  line of silicon element detected by fluorescent X-ray analysis of a surface on the first dielectric layer side of the first hard coat layer is 15 to 35 cps.

